

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1 – 4 (Cancelled)

5. (Currently amended) ~~An expansive element in a A thermoelastic design actuator that is made from a~~ comprises an expansive element of a material or combinations of materials selected from a group including silicides and carbides of titanium, ~~the material or combination of materials being selected to have having one or more of the following properties:~~

- (a) a resistivity between $0.1\mu\Omega\text{m}$ and $10.0\mu\Omega\text{m}$; and being
- (b) chemically inert in air; ,
- (c) ~~chemically inert in ink; and~~
- (d) ~~depositable by CVD, sputtering or other thin film deposition technique.~~

6. (Cancelled)

7. (Currently amended) ~~An expansive element in a A thermoelastic design actuator that is made from~~ comprises an expansive element of a material or combinations of materials selected from a group including borides, silicides, carbides and nitrides of tantalum, molybdenum, niobium, chromium, tungsten, vanadium, and zirconium, ~~and having one or more of the following properties:~~

- (e) a resistivity between $0.1\mu\Omega\text{m}$ and $10.0\mu\Omega\text{m}$; and being
- (f) chemically inert in air; ,
- (g) ~~chemically inert in ink; and~~
- (h) ~~depositable by CVD, sputtering or other thin film deposition technique.~~

8. (Cancelled)

9. (Currently amended) ~~An expansive element in a A thermoelastic design actuator that is made from~~ comprises an expansive element of an alloy material or combinations of alloy materials selected from the group including: borides, silicides, carbides and nitrides of titanium, tantalum, molybdenum, niobium, chromium, tungsten, vanadium, and zirconium, ~~and having one or more of the following properties:~~

- (i) a resistivity between $0.1\mu\Omega\text{m}$ and $10.0\mu\Omega\text{m}$; and being
- (j) chemically inert in air; ,
- (k) ~~chemically inert in ink; and~~
- (l) ~~depositable by CVD, sputtering or other thin film deposition technique.~~

10. (Cancelled)

11. (New) An actuator as claimed in claim 5, in which the materials or combinations of material are chemically inert in ink and are depositable by CVD, sputtering or other thin film deposition techniques.

12. (New) An actuator as claimed in claim 7, in which the materials or combinations of material are chemically inert in ink and are depositable by CVD, sputtering or other thin film deposition techniques.

13. (New) An actuator as claimed in claim 9, in which the alloy material or combinations of alloy materials are chemically inert in ink and are depositable by CVD, sputtering or other thin film deposition techniques.